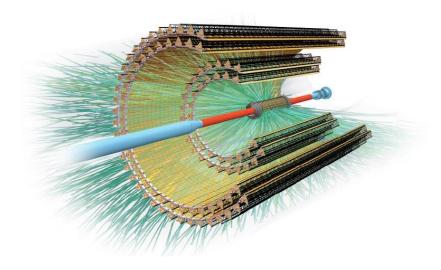


Update on Pixel Chip for the ALICE ITS Upgrade

Luciano Musa - CERN



LHCC Week – Detector Upgrade Session 1st December 2015

Update on the Pixel Chip for the ALICE ITS Upgrade

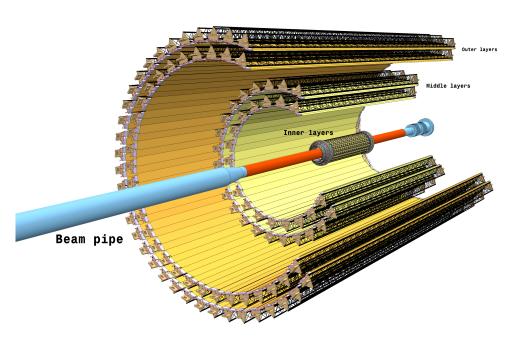
A Large Ion Collider Experiment



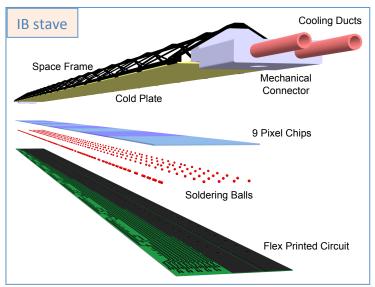
OUTLINE

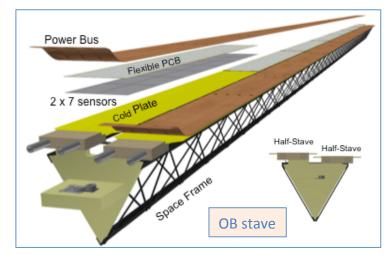
- ITS layout and Pixel Chip General Requirements
- Pixel Chip (ALPIDE) Overview and Status
- pALPIDE-2 Main Design Features and Performance
- Engineering Design Review
- pALPIDE-3 Preliminary Results
- Towards final chip





- ► 7-layer barrel based on CMOS sensors
- ► Radial coverage 22 400 mm
- ► Total active area ~10m²
- ~ 24,000 pixel chips (12.5 G pixels)
- Radiation: ~2.7 Mrad (~1.7x10¹³ 1MeV n_{eq}/cm²) including safety factor 10





PIXEL Chip – General Requirements



General Requirements and ALPIDE Specifications^(*)

| Parameter | Inner Barrel | Outer Barrel | |
|---|--|------------------------|--|
| Chip size (mm x mm) | 15 x 30 | | |
| Chip thickness (µm) | 50 | 100 | |
| Spatial resolution (μm) | 5 | 10 (5) | |
| Detection efficiency | > 99% | | |
| Fake hit rate | < 10 ⁻⁵ evt ⁻¹ pixel ⁻¹ (>> ALPIDE) | | |
| Integration time (μs) | < 30 (< 10) | | |
| Power density (mW/cm²) | < 300 (~35) | < 100 (~20) | |
| TID radiation hardness (krad) (*) | 2700 | 100 | |
| NIEL radiation hardness (1MeV n _{eq} /cm ²) (**) | 1.7 x 10 ¹³ | 1.7 x 10 ¹² | |

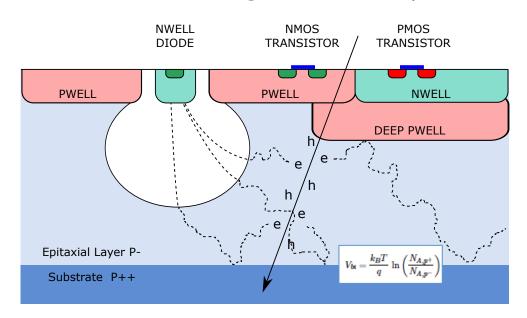
^(*) Colour code: ALPIDE specifications if different from requirements

^{(**) 10} x radiation load integrated over approved programme (~ 6 years of operation)

ITS Pixel Chip – technology choice



CMOS Pixel Sensor using TowerJazz 0.18µm CMOS Imaging Process



Tower Jazz 0.18 µm CMOS

feature size 180 nm

metal layers

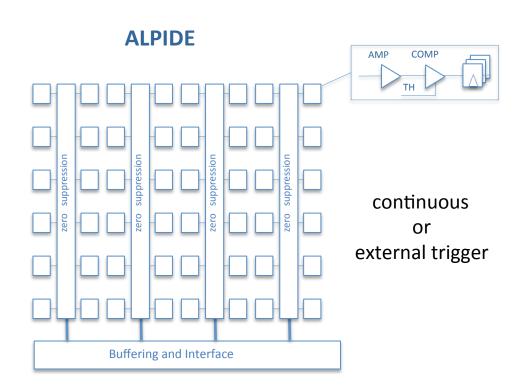
gate oxide 3nm

substrate: $N_{\Delta} \sim 10^{18}$ epitaxial layer: $N_{\Delta} \sim 10^{13}$ deep p-well: $N_{\Lambda} \sim 10^{16}$

- High-resistivity (> $1k\Omega$ cm) p-type epitaxial layer ($18\mu m$ to $30\mu m$) on p-type substrate
- Small n-well diode (2 μ m diameter), ~100 times smaller than pixel => low capacitance
- Application of (moderate) reverse bias voltage to substrate (contact from the top) can be used to increase depletion zone around NWELL collection diode
- Deep PWELL shields NWELL of PMOS transistors to allow for full CMOS circuitry within active area

ITS Pixel Chip - ALPIDE





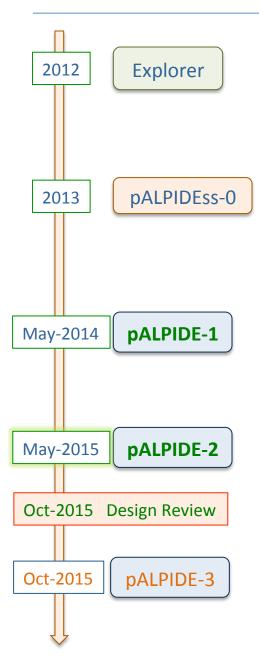
Architecture

- In-pixel amplification
- ► In-pixel discrimination
- ► In-pixel (multi-) hit buffer
- ► In-matrix sparsification

Key Features

- ⊙ 28 μm x 28 mm pixel pitch
- Continuously active, ultra-low power front-end (40nW/pixel)
- No clock propagation to the matrix → ultra-low power matrix readout (2mW whole chip)
- \odot Global shutter (<10 μ s): triggered acquisition or continuous

ALPIDE Development



- 20μm x 20μm and 30μm x 30μm pixels (analogue readout)
- pixel geometry, starting material, sensitivity to radiation
- Matrix with 64 columns x 512 rows
- 22μm x 22μm pixels
- (in-pixel discrimination and buffering)
- zero suppression within pixel matrix
 - Full-scale prototype: 1024 x 512
 - 4 sectors with different pixels
 - pixel pitch: 28μm x 28μm
 - 1 register/pixel, no final interface



11 mm

- Optimization of several circuit blocks
- | final interface: allows integration into ITS modules
- NO high-speed output link (1.2 Gbit/sec replaced by a 40Mb/s)
- 8 sectors with different pixel variants, 3 registers / pixel
- Final interfaces, more features including 1.2 Gbit/s output serial link
- Some optimization for yield improvement
- Characterization ongoing

1.8mm

pALPIDE-1&2 – Main Design Features

A Large Ion Collider Experiment



ALPIDE full-scale prototypes vers. 1 (2014) and ver.2 (2015)

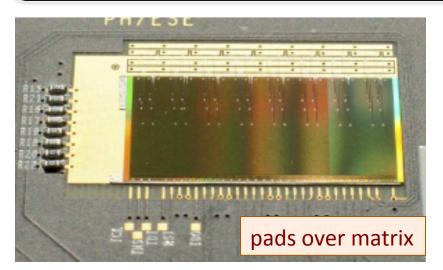


Figure: picture of pALPIDE-2

Main parameters

Dimensions: 30mm x 15 mm

Pixel Matrix: 1024 cols x 512 rows

• Pixel pitch: 28μm x 28μm

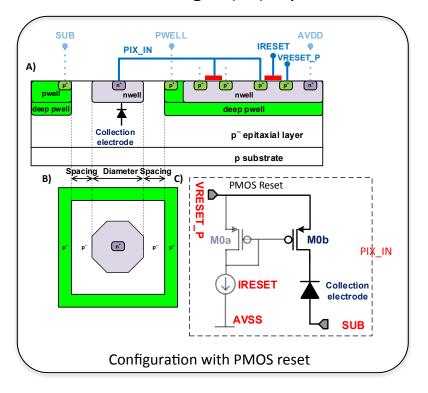
• Integration time: <10μs

• Power consumption: < 40mW/cm²

• 4 sectors with different pixels

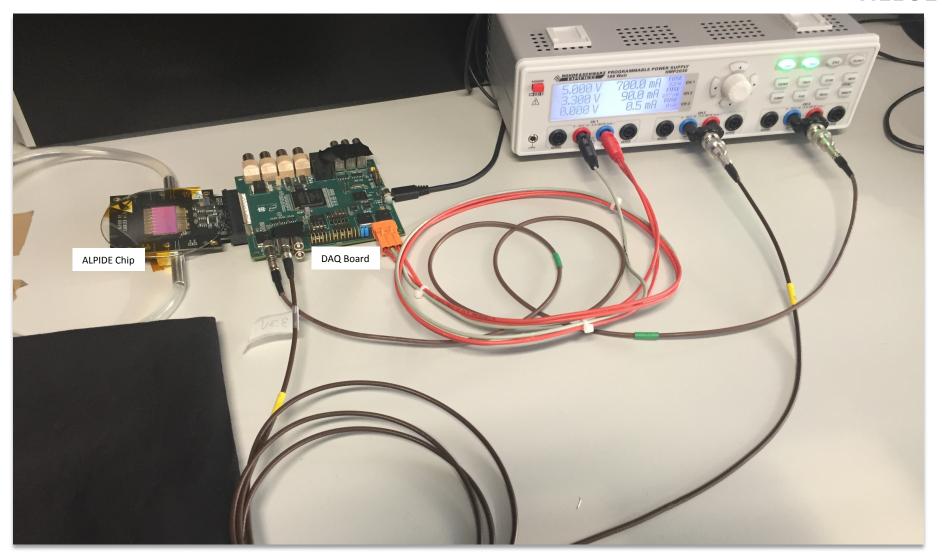
Matrix divided in 4 sectors, each with 256 cols x 512 rows

- Collection node: octagonal 2μm diameter
- Spacing NWELL and PWELL: 2μm to 4μm
- 2 reset mechanism: diode, PMOS
- 1 sector with larger (x2) input transistor



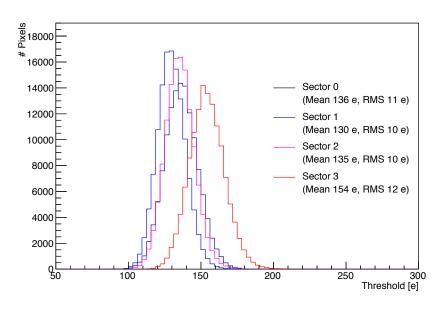
ALICE

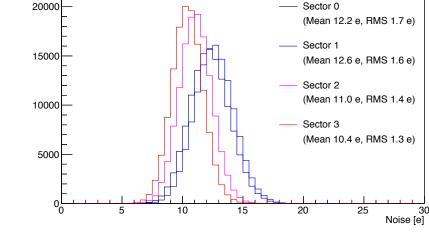
Laboratory Measurements → e.g. noise and thresholds





Example of Threshold and Noise Distributions





$$V_{SUB} = -3V$$
, $I_{THR} = 0.5$ nA, $V_{CASN} = 0.95$ V

- ► All sectors behave qualitatively similarly
- Noise is about the same value as threshold RMS
- ► Threshold about 10 x higher than noise
- Threshold 7 x smaller than most-probable energy loss signal of a MIP in 18μm of silicon

<u>s</u>25000 <u>s</u>25000 <u>s</u>1 d. #



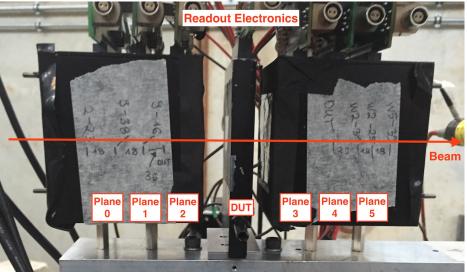
Test Beam Set-up

- ▶ 6 GeV/c π beam at CERN PS
- ▶ 6 reference planes based on pALPIDE-1
- Single pALPIDE-2 as Device Under Test (DUT) in the center
- Track resolution of about 2.8μm (<< 28μm)

Analysis Method

- Extrapolate track from referecne planes trough DUT
- ▶ Search for clusters next to extrapolated impinging point → detection efficiency
- Obtain cluster size
- Compare extrapolated and actual position
 position resolution

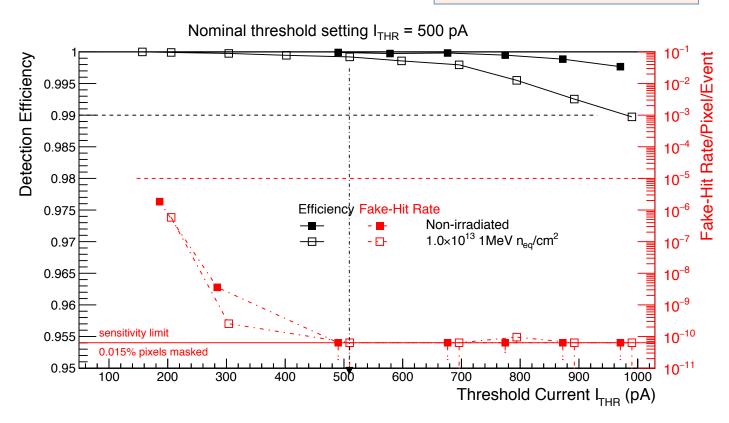




ALICE

Efficiency and fake hit rate

epi=25 μ m, V_{BB}=-6V, spacing=2 μ m



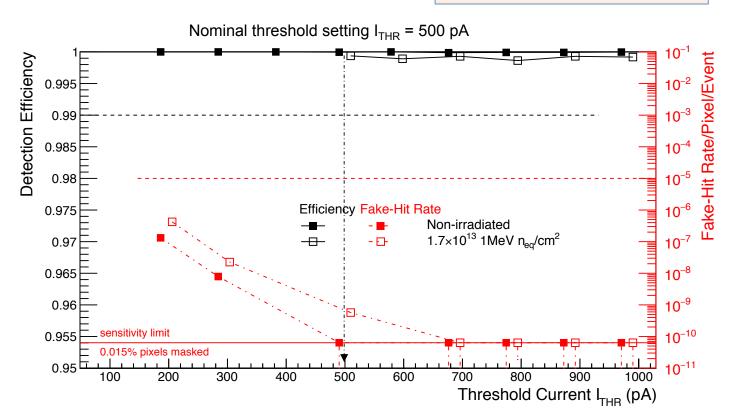
 $\epsilon_{\rm det}$ > 99% @ $\lambda_{\rm fake}$ < < 10⁻⁵ / event/pixel \Rightarrow large margin over design requirements

• Results refer to chips with 25 μ m high-res epi layer, thinned to 50 μ m: 1 non irradiated and 1 irradiated with 10¹³ 1MeV n_{eq} / cm²

ALICE

Efficiency and fake hit rate

epi=30 μ m, V_{BB}=-6V, spacing=4 μ m



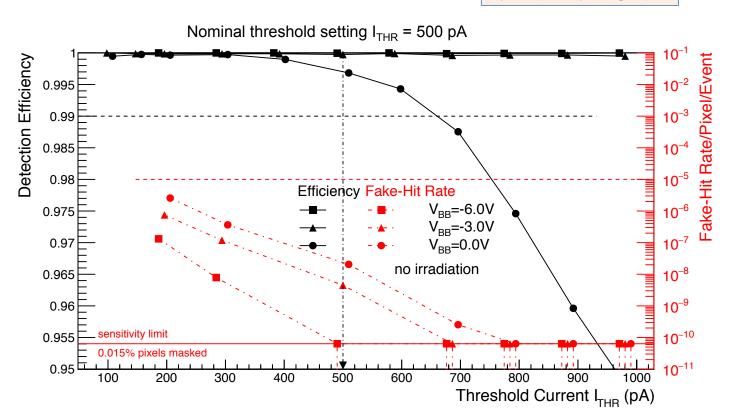
Even larger operation margin for $30\mu m$ epi layer and $4\mu m$ spacing

• Results refer to chips with 30 μ m high-res epi layer, thinned to 50 μ m: 1 non irradiated and 1 irradiated with 10¹³ 1MeV n_{eq} / cm²



Efficiency and fake hit rate

epi=30μm, spacing=4μm



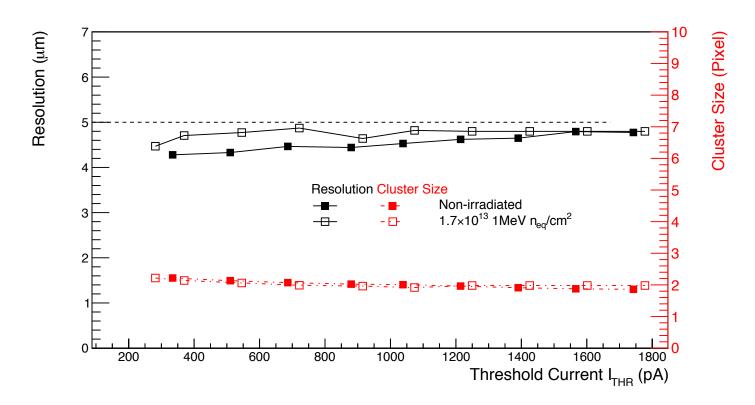
operation margin significantly increased reverse bias voltage

• Results refer to chips with $30\mu m$ high-res epi layer, thinned to $50 \mu m$



Spatial Resolution and Cluster Size

epi=30 μ m, V_{BB}=-6V, spacing=4 μ m



 $\sigma_{det} \approx 5 \ \mu m$ is achieved before and after irradiation

• Results refer to chips with 30 μ m high-res epi layer, thinned to 50 μ m 1 non irradiated and 1 irradiated with 1.7x10¹³ 1MeV n_{eq} / cm²

EDR: pALPIDE-2 results and pALPIDE-3 design

A Large Ion Collider Experiment



EDR (19 Oct 2015) - Review panel: A. Marchioro (CERN), W. Mueller (GSI), X. Llopart (CERN)

General Assessment

"The reviewers were impressed by the amount and the quality of information provided by the design team for the review. The design team has clearly worked very hard and thoroughly for this project and was orchestrated very competently and effectively by its management team.

The Alice ITS project aims at introducing some very original solutions in the area of pixelated detectors for particle physics, in particular the new technology, the sensor architecture, the extremely low power front-end circuitry and the mechanical thinning of the detector, all are pioneering significant innovations.

Unavoidably innovations cannot be decoupled from risks, but it seems to these reviewers that the team has studied in detail the various aspects of the design of the proposed chip and has used extensively simulation tools to understand its behavior. Of course the usage of simulation tools must be accompanied by and the results digested with a fair amount of common sense, which has been expressed during the review. The engineering team has shown to have worked proactively on a number of issues that were raised during the presentation.

It is also fair to notice that the learning in a new and very promising monolithic technology that this project will hopefully bring to the HEP community does by itself partly justify the risk taken with the project.

Finally, it was really a pleasure to see the enthusiasm and competence of the overall team working on this project."



First Laboratory Results

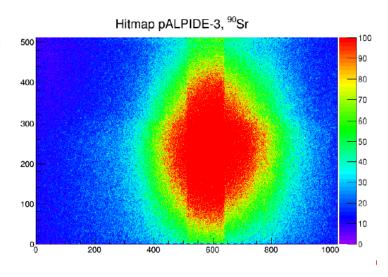
- 29 chips mounted on carrier boards (12 x 18μm, 8 x 25μm, 9 x 30μm)
- ▶ 4 chips non working (still to verify whether is the chip or the assembly)
- ≥ 25 chips are working in standard tests (→ 86% yield)

Irradiation tests

- Chips irradiated with neutrons and ionizing radiation
- ▶ Done first campaign of SEU/SEL measurements

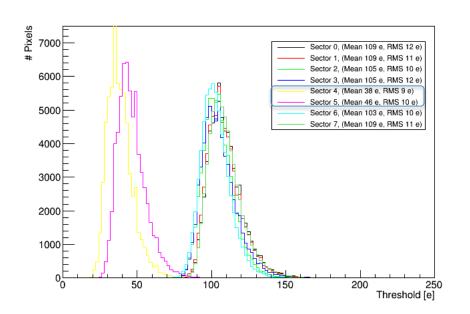
Test beam

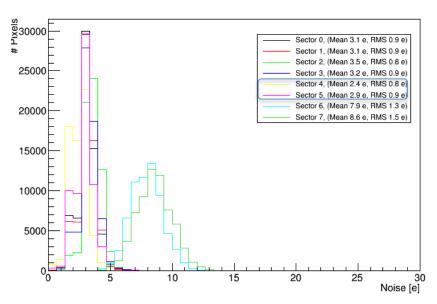
- Only 1 day of test beam at the PS
- Few measurements on one chip (18 μ m, V_{SUB} =0)
- → Systematic test ongoing in laboratory
- → Next test beam in Frascati starting on 7 December





Example of Threshold and Noise Distributions



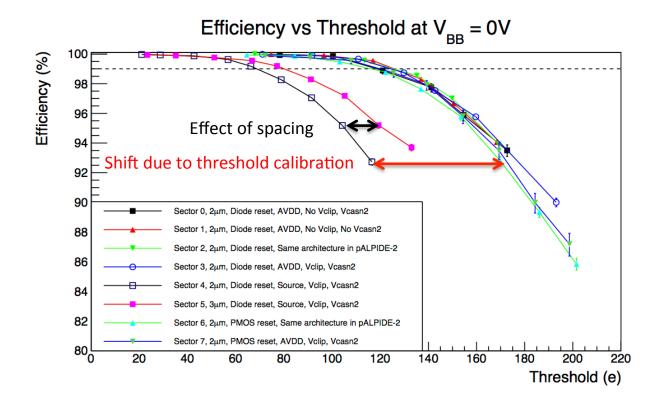


- ► Thresholds (left) and Noise (right) distributions for all sectors (ITRH=51)
- ► Sector 4 and 5 show lower thresholds due to (expected) higher gain
- Sector 6 and 7 PMOS reset, all others diode reset



pALPIDE-3 PS test beam

- ▶ 1 chip tested for one day (last day of PS test beam)
- Measurements with NO reverse bias voltage

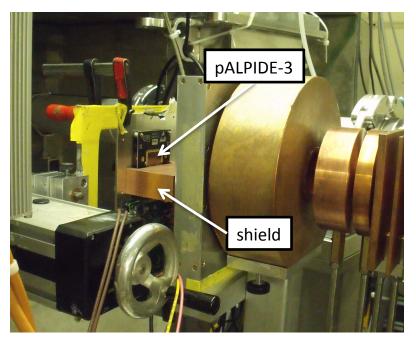


A Large Ion Collider Experiment

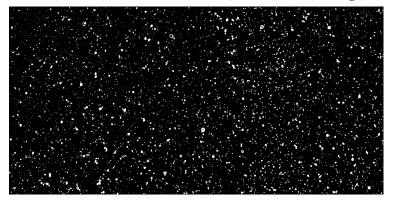


Single Event Upset - Setup

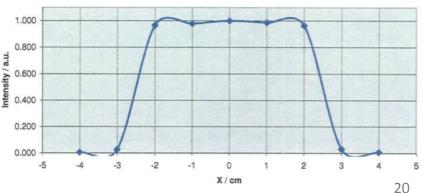
- Proton Irradiation Facility (PIF) @ PSI
- 200 MeV protons
- $1.6 \times 10^8 \text{ p/cm}^2$
- Widened beam to cover full pALPIDE-3 chip
- Chip connected to standard readout system
- Cross-sections measured by digitally stimulating the pixels
- Unmasking cross-section verified by looking at beam particles



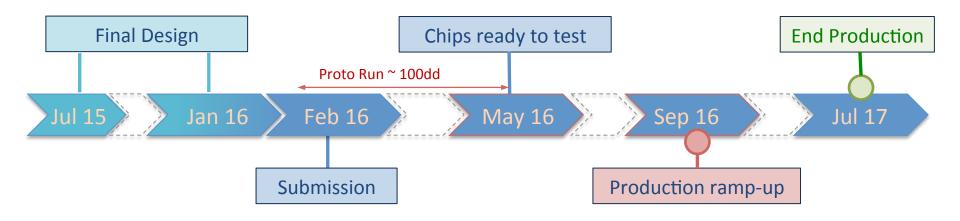
Picture of one event (w/o masking)



X-profile







ALPIDE finalization and production timeline

- ► Enineering Design Review: Oct 15
- Complete design of final ALPIDE: Jan 16
- ▶ Proto-run: Feb May 16
- Production Readiness Review: July 16
- ► Series Production (~25 wafer/week): Sep 16 Jul 17

Spare Material

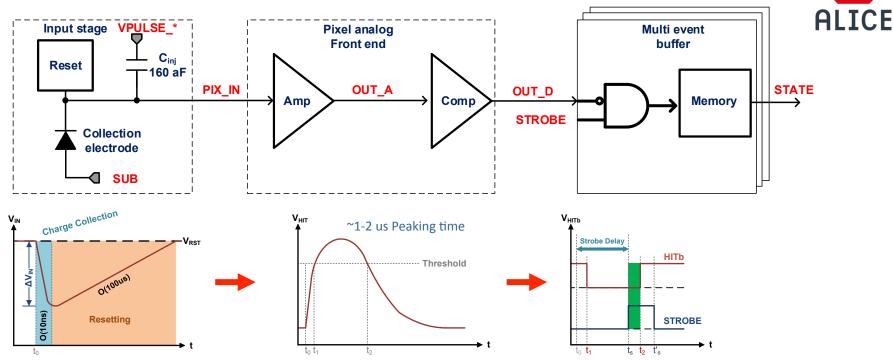
ALPIDE (4) Design Finalization



Main Design Activities (changes) wrt pALPIDE-3 (including EDR recommendations)

- Select final pixel (collection diode + front-end circuit)
- Improve detailed routing of pixel configuration control wires under Pads Over Circuits
- ► Improve handling of pixel configuration signals from periphery (EDR rec.)
 - Enable fast reload of pixel mask even during readout. Support active forcing of the mask bits from periphery
- Optimize distribution of global STROBING and PULSING signals from periphery (EDR recommendation)
 - Enable major speed-up of pixel tests with analogue scans and charge injection
 - Optimize supply current time profile (phase shift pulses in time) (EDR rec.)
- Power optimization of digital block (clock gating)
- Data Transmission Unit: power optimization
- ► MLVDS: experimental verification of new version with module power off protection
- ► I/O CMOS: re-simulation to evaluate signal integrity (EDR recommendation)
- POWER-ON RESET: triplication (together with global reset signals) (EDR recommendation)





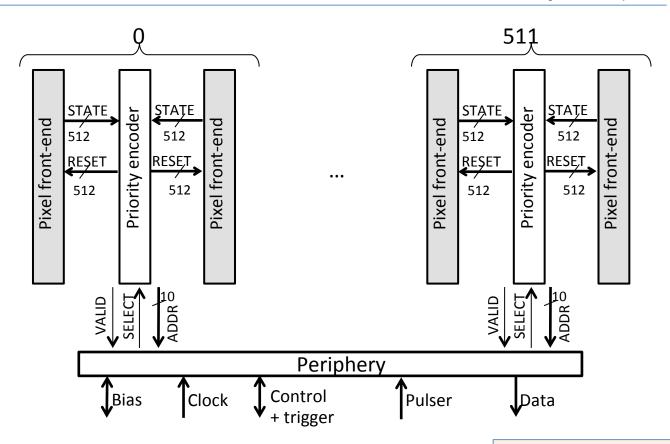
Front-end acts as delay line

- Sensor and front-end continuously active
- Upon particle hit front-end forms a pulse with ~1-2µs peaking time
- Threshold is applied to form binary pulse
- Hit is latched into a (3-bit) memory if strobe is applied during binary pulse

ultra low-power front-end circuit 40nW / pixel

ALPIDE Principle of Operation





Pixel Matrix - Hit driven architecture

low-power matrix readout ~ 2mW

- Priority encoder sequentially provides addresses of all hit pixels present in double column
- No activity if no hit (no free running clock) → low power



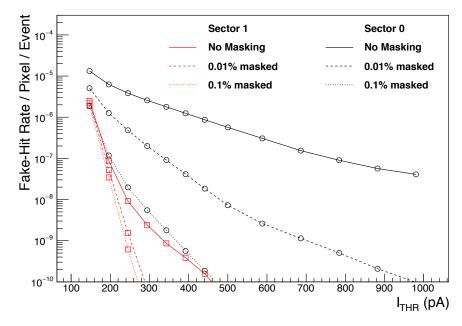
Fake-Hit Rate Measurements

- ▶ 120,000 (pseudo) random triggers
- No external signal
- Offline masking of 0.15% of the hottest pixels (20 per sector)
- Measurement reach / sensitivity limit

$$p_{\min} = \frac{1}{N_{Event} \cdot N_{Pixel}}$$

$$=6.36 \cdot 10^{-11} / Pixel / Event$$

 Larger size input transistor (sector 1) reduces fake-hit rate significantly

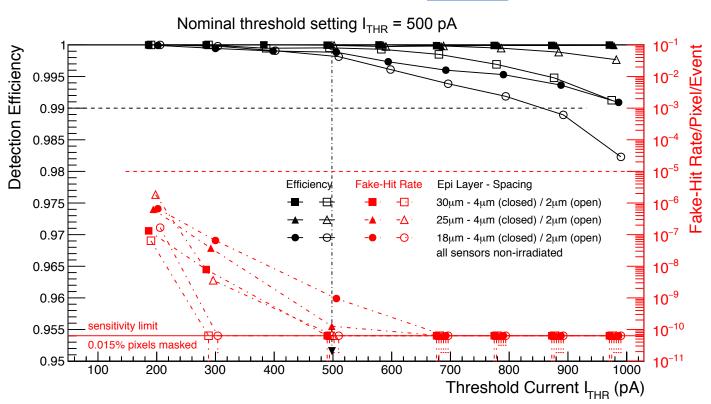


8 chips,
$$V_{SUB} = -3V$$
, $I_{THR} = 0.5$ nA, $V_{CASN} = 0.95V$



Efficiency and Fake Hit Rate





Larger "spacing" shows better detection efficiency

• Results refer to chips with 30 μ m high-res epi layer, thinned to 50 μ m



Single Event Upset - Results

 Cross-sections of data memories validated:

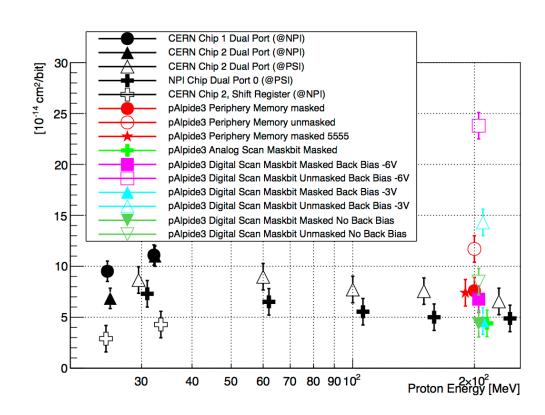
$$\sigma_{\rm DP} \approx (4-8) \times 10^{-14} \, \rm cm^2/bit$$

 Cross-section of mask register comparable to standard-cell version:

$$\sigma_{FF,OV} \approx (4-8) \times 10^{-14} \text{ cm}^2/\text{bit}$$
 (at OV back-bias)

 Cross-section increases with backbias.
 Upper limit:

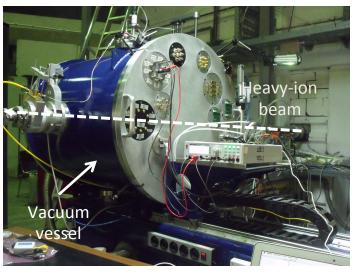
$$\sigma_{FF,6V}$$
<2.5×10⁻¹³ cm²/bit

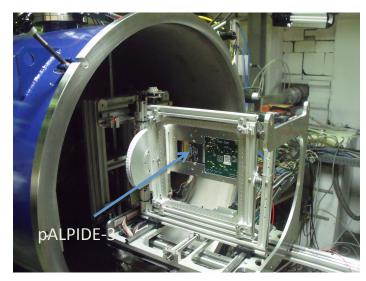




Single Event Latchup - Setup

- Heavy Ion Irradiation Facility (HIF) at Louvain-La-Neuve
- Particle flux: 10⁴/cm²/s
- LETs: 10.0, 20.4, 32.5, and 62.5 MeV cm²/mg
- First test: no back-bias

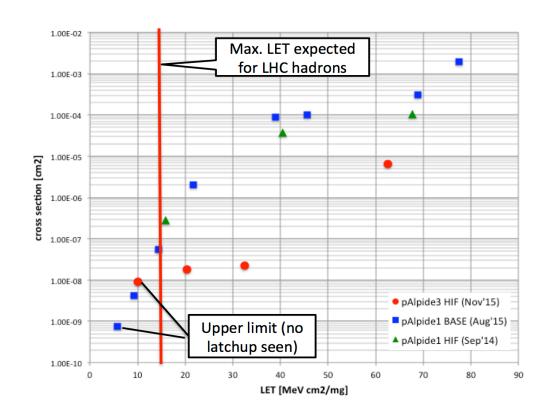






Single Event Latchup – Preliminary Results

- Analogue latch-up (present in pALPIDE-1) have disappeared as effect of the modifications implemented
- Cross-section reduced by 1-4 orders of magnitude



A Large Ion Collider Experiment



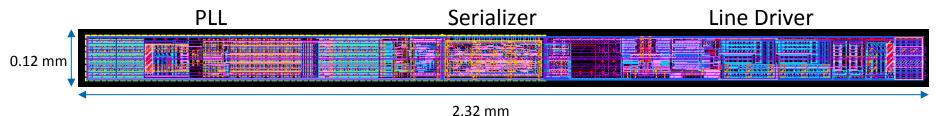
DTU – Data Transmission Unit (HSO)

DTU v2b

Implemented in pALPIDE-3 (June 2015)

Layout 2.32 mm \times 0.12 mm

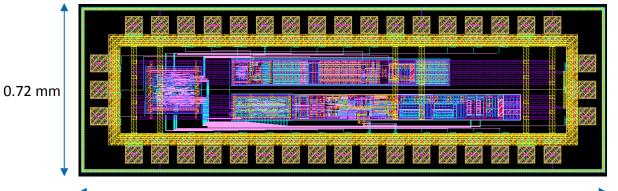
Includes PLL + Serializer + Driver + Test Features



2.52 11111

DTU v2b Test Chip

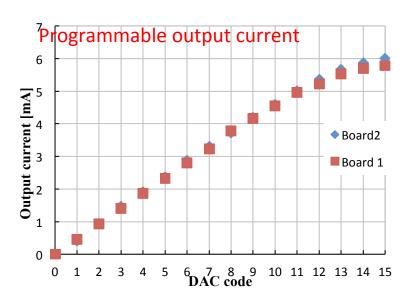
Submitted together with pALPIDE-3



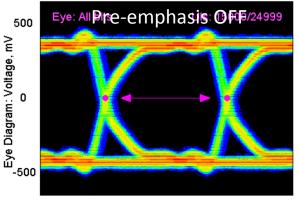


DTU – Laboratory characterization

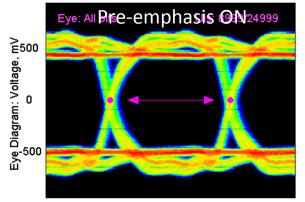
- Full DTU chain functional (PLL+Serializer+Driver)
 - Test Chip Carrier + External clock source +
 Coax cables + Scope



Programmable Pre-Emphasis Current



-800ps600ps400ps200ps0ps 200ps400ps600ps800ps

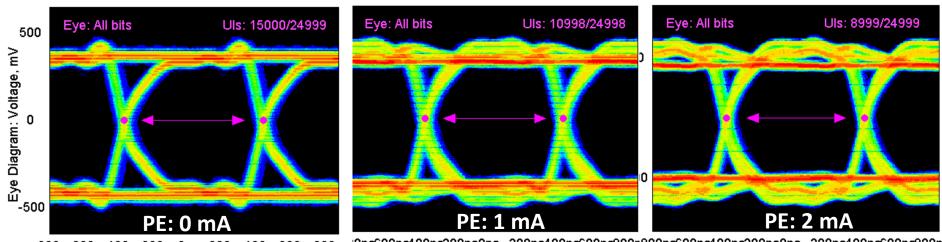


-800ps600ps400ps200ps0ps 200ps400ps600ps800ps



DTU – Laboratory characterization

Eye diagrams vs Pre-Emphasis



 $-800 ps\!600 ps\!400 ps\!200 ps\!0ps \\ 200 ps\!400 ps\!600 ps\!800 ps\!$

Bit rate: 1.25 Gb/s

Main driver current setting: 4 mA

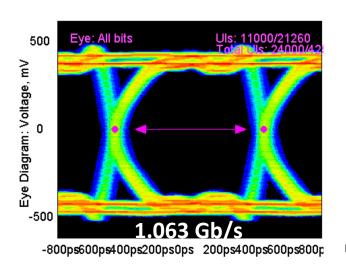
| Pre Emphasis | 0 mA | 1 mA | 2 mA |
|----------------------|----------|----------|----------|
| Eye width | 0.822 UI | 0.826 UI | 0.835 UI |
| Eye opening | 0.738 UI | 0.742 UI | 0.716 UI |
| Random jitter | 11.4 ps | 10.9 ps | 12.0 ps |
| Deterministic jitter | 48.8 ps | 52.8 ps | 57.4 ps |

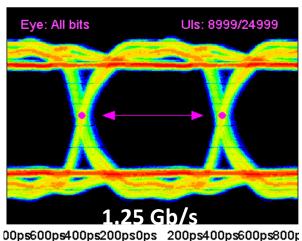
UI, Unit Interval: 1/1.25 Gbps = 0.8 ns

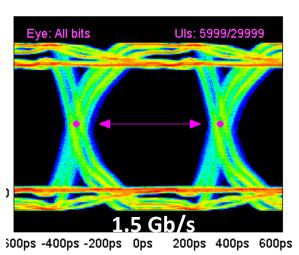


DTU – Laboratory characterization

Eye diagrams vs Bit Rate







Nominal (mid range) settings for main driver current and pre-

emphasis current

| | 1.25 Gb/s | 1.063 Gb/s | 1.5 Gb/s |
|----------------------|-----------|------------|----------|
| Eye width | 0.835 UI | 0.820 UI | 0.779 UI |
| Eye opening | 0.716 UI | 0.713 UI | 0.707 UI |
| Random jitter | 12.0 ps | 13.5 ps | 8.0 ps |
| Deterministic jitter | 57.4 ps | 64.6 ps | 82.6 ps |